- 1. A retaining ring comprising:
- a generally annular body having a top surface, a bottom surface, an inner diameter surface, and an outer diameter surface, wherein the bottom surface includes a plurality of channels, each channel extending from the inner diameter surface to the outer diameter surface and having a rounded ceiling.
 - 2. The retaining ring of claim 1, wherein the rounded ceiling has a semicircular cross-section.
- The retaining ring of claim 2, wherein the semi-circular cross-section has a diameter about equal to a width of the channel.
 - 4. The retaining ring of claim 1, wherein the rounded ceiling has a flat portion.
 - 5. The retaining ring of claim 4, wherein the rounded ceiling is rounded at an intersection of the flat portion and vertical side-walls of the channel.
- 6. The retaining ring of claim 1, wherein each channel includes substantially vertical side-walls.
 - 7. The retaining ring of claim 1, wherein the plurality of channels have substantially uniform depth.
- 25 8. The retaining ring of claim 1, wherein the plurality of channels are oriented at an angle relative to a radial segment extending through the center of the retaining ring.
 - 9. The retaining ring of claim 8, wherein the angle is between 30° and 60°.

5

15

- 10. The retaining ring of claim 1, wherein the outer diameter surface includes a ledge.
- The retaining ring of claim 10, wherein the outer diameter surface includes a first portion adjacent the bottom surface that has an outer diameter less than a second portion adjacent the top surface.
 - 12. The retaining ring of claim 10, wherein the each channel includes substantially vertical side-walls, the side walls extending to substantially the same depth as the ledge.
 - 13. The retaining ring of claim 1, wherein the annular body comprises a wearable material.

10

25

- 14. The retaining ring of claim 1, wherein the annular body comprises an upper portion and a lower portion, the upper portion being more rigid than the lower portion.
- 15. The retaining ring of claim 14, wherein the channels are formed in the lower portion.
 - 16. The retaining ring of claim 15, wherein the lower portion is formed of a wearable material.
 - 17. The retaining ring of claim 15, further comprising a plurality of passages extending through the upper portion from the inner diameter surface to the outer diameter surface.
- 18. The retaining ring of claim 1, wherein the plurality of channel are distributed at substantially equal angular intervals around the retaining ring.

19. A carrier head comprising:

a substrate receiving surface;

5

10

15

a generally annular retaining ring surrounding the substrate receiving surface, the retaining ring having a top surface, a bottom surface, an inner diameter surface, and an outer diameter surface, wherein the bottom surface includes a plurality of channels, each channel extending from the inner diameter surface to the outer diameter surface and having a rounded ceiling.

20. A method of polishing, comprising:

creating relative motion between a substrate and a polishing surface;

restraining the substrate with retaining ring that has a top surface, a bottom surface, an inner diameter surface, and an outer diameter surface, wherein the bottom surface includes a plurality of channels, each channel extending from the inner diameter surface to the outer diameter surface and having a rounded ceiling; and

supplying a polishing liquid to the polishing surface so that the polishing liquid flows through the channels and beneath the retaining ring to the substrate.